
ICPST-39

The 39th International Conference of Photopolymer Science and Technology

Materials & Processes for Advanced Lithography,
Nanotechnology and Phototechnology

June 27 - 30, 2022
International Conference Hall
Makuhari Messe, Chiba, Japan

The details will be announced later in our WEB site
(<https://www.spst-photopolymer.org>).

Scopes

A. English Symposia

- A1. Next Generation Lithography, EB Lithography and Nanotechnology
- A2. Nanobiotechnology
- A3. Directed Self Assembly (DSA)
- A4. Computational / Analytical Approach for Lithography Processes
- A5. EUV Lithography
- A6. Nanoimprint
- A7. 193 nm Lithography Extension and EUV HVM Readiness
- A8. Photopolymers in 3-D Printing/ Additive Manufacturing
- A9. 2D and Stimuli Responsive Materials for Electronics & Photonics
- A10. Strategies and Materials for Advanced Packaging, Next Generation MEMS, Flexible Devices
- A11. Chemistry for Advanced Photopolymer Science
- A12. Organic and Hybrid Materials for Photovoltaic and Optoelectronic Devices
- A13. Fundamentals and Applications of Biomimetics Materials and Processes
- A14. General Scopes of Photopolymer Science and Technology
- P. Panel Symposium "Beyond Sub-10 nm Lithography -From a Material Design and Development Perspective-"

B. Japanese Symposia

- B1. Polyimides and High Thermally Stable Resins
-Functionalization and Practical Applications-
- B2. Plasma Photochemistry and Functionalization of Polymer Surfaces
- B3. General Scopes of Photopolymer Science and Technology

Deadline of application to scientific program

February 14, 2022.

Deadline of submission of papers

April 1, 2022.

Deadline of registration for participants

May 25, 2022

ICPST-39

第39回 国際フォトポリマーコンファレンス

リソグラフィー、ナノテクノロジー、フォトテクノロジー
-材料とプロセスの最前線-

2022年6月27日(月)～30日(木)
千葉市・幕張メッセ国際会議場

詳細は学会のホームページ(<https://www.spst-photopolymer.org>)
でご案内します

スコープ

A. 英語シンポジウム

- A1. Next Generation Lithography, EB Lithography and Nanotechnology
- A2. Nanobiotechnology
- A3. Directed Self Assembly (DSA)
- A4. Computational / Analytical Approach for Lithography Processes
- A5. EUV Lithography
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- P. Panel Symposium "Beyond Sub-10 nm Lithography -From a Material Design and Development Perspective-

B. 日本語シンポジウム

- B1. ポリイミド及び高温耐熱樹脂-機能化と応用
- B2. プラズマ光化学と高分子表面機能化
- B3. 一般講演：(1) 光物質科学の基礎（光物理過程、光化学反応など）、(2) 光機能素子材料（分子メモリー、情報記録材料、液晶など）、(3) 光・レーザー電子線を活用する合成・重合・パターンニング、(4) フォトファブリケーション（光成型プロセス、リソグラフィ）、(5) レジスト除去、エッチング、洗浄、(6) 装置（光源、照射装置、計測、プロセスなど）

講演申込締切 2022年2月14日(月)

論文原稿締切 2022年4月1日(金)

参加申込予約締切 2022年5月25日(水)